IN THE SPECIFICATION

Please amend the Abstract as follows:

The present invention provide discloses a ceramic substrate for semiconductor manufacture and/or inspection which is conducive to decrease in α -rays radiated α -rays[[,]] and change to minimize changes in of thermal conductivity with passage of the as a function of time, thereby yielding a and which is superior in the temperature controllability. This invention is related to a ceramic substrate for apparatuses for use in semiconductor manufacture and/or inspection, Wherein wherein the level of α -rays radiated from said ceramic substrate exceeds 0.25 c/cm²·hr and is not higher than 50 c/cm²·hr.